## PATENT ABSTRACTS OF JAPAN

(11)Publication number

(43)Date of publication of application:

12.09.1995

(51)IntCL

GD2F 1/136 GD2F 1/1343 HO1L 29/786

(21)Application number: 06-031545

(71)Applicant

HITACHI LTD

(22) Date of filing:

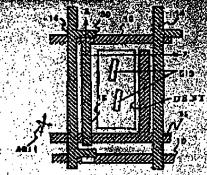
01.03.1994

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## (64) LIQUID CRYSTAL DISPLAY SUBSTRATE

(\$7)Abstract:
PURPOSE: To improve, a response speed and contrast ratio by forming dents in the region within a plane contrast and electrodes. CONSTITUTION: Gate electrodes 10 and common electrodes 16 consisting of C. are formed an a glass substrate and gate insulating films consisting of silicon mends films are so formed as to took these electrodes. Amorphous silicon films 30 are formed via the gate insulating films on a part on the gate electrodes 10 and are used as active layers of transistors. The dents DENTS are formed in the regions within the plane inclusive of a pair of such electrodes. The more bomponents of the transverse direction (direction connecting the respective electrodes) of electric fields generated between the respective electrodes of a pair of the electrodes are eventually uspable of passing liquid crystals. The liquid crystals are packed into the regions formed with these dents DENTs and the packed liquid crystal layers are eventually brought into proximity with the plane contrast a pair of the electrodes or are made to exist down to the lower side (transparent substrate surface side formed with a pair of the electrodes) of the plane. Then, the response speed of the liquid crystals is improved and the sufficient contrast ratio is obtd.



## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection

[Date of requesting appeal against examiner's decision of rejection

[Date of extinction of right]

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